



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No. : 10/670,744 Confirmation No. : 2746
Applicant : SATORU KOBAYASHI, et al.
Filed : September 26, 2003
TC/A.U. : 1621
Examiner : Not assigned
Docket No. : 038788.52799US
Customer No. : 23911
Title : FLUORINE-CONTAINING ALLYL ETHER
COMPOUNDS, THEIR COPOLYMERS, AND RESIST
COMPOSITIONS AND ANTI-REFLECTION FILE
MATERIAL USING SUCH COPOLYMERS

**INFORMATION DISCLOSURE STATEMENT
UNDER 37 CFR §§ 1.97 and 1.98**

Mail Stop Missing Parts
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In accordance with the duty of disclosure under 37 CFR §1.56, Applicant hereby notifies the U.S. Patent and Trademark Office of the document which is listed on the attached Form PTO-1449 and/or listed herein and which the Examiner may deem relevant to patentability of the claims of the above-identified application.

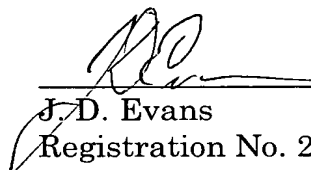
The relevance of this reference to the subject matter of the present invention is given in the Background of the Invention in the specification of the present invention.

The present Information Disclosure Statement is being filed before the mailing date of the first Office Action on the merits, and therefore no certification under 37 C.F.R. §1.97(e) or fee under 37 C.F.R. §1.17(p) is required.

The submission of the listed documents is not intended as an admission that any such document constitutes prior art against the claims of the present application. Applicant does not waive any right to take any action that would be appropriate to antedate or otherwise remove any listed document as a competent reference against the claims of the present application.

Respectfully submitted,

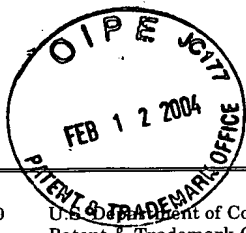
February 12, 2004



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FORM PTO-1449 U.S. Department of Commerce Patent & Trademark Office	Attorney Docket No. 038788.52799US	Serial No. 10/670,744
	Applicant: Satoru KOBAYASHI, et al.	
	Filing Date: September 26, 2003	Group:

INFORMATION DISCLOSURE STATEMENT
(Use several sheets if necessary)

U.S. PATENT DOCUMENTS							
Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date (if appropriate)
	AA						
	AB						
	AC						
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	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						

FOREIGN PATENT DOCUMENTS								
Examiner Initial		Document Number	Date	Country	Class	Sub- Class	TRANSLATION	
							Yes	No
	AK							
	AL							
	AM							
	AN							
	AO							
	AP							

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)		
AQ	Kamon, et al., "Newly Developed Acrylic Copolymers for ArF Photoresist", <i>Journal of Photopolymer Science and Technology</i> , Vol. 15, No. 4 (2002), pp. 535-540	
AR		
AS		

EXAMINER	DATE CONSIDERED
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication.	